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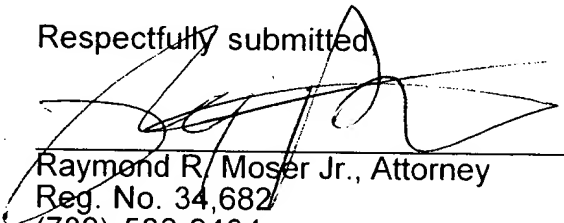
processing system 100 contains one or more metrology chambers or stations within which defect and defect source information is generated. The local database 114<sub>n</sub> stores this defect and defect source data. The information from the client database 114, either all or a subset thereof, is communicated to the DKL 102 via the network 104. The subscriber controls the specific amount of data that is communicated to the DKL 102. A distributed defect source analysis system such as the one depicted in Figure 1 is disclosed in US patent application serial number 09/905,607, filed simultaneously herewith on July 13, 2001, and incorporated herein by reference in its entirety.

REMARKS

The above amendments have been made to add the appropriate serial numbers to the specification.

If the Examiner believes that there are any unresolved issues, it is requested that the Examiner telephone Raymond R. Moser Jr. at (732) 530-9404 so that appropriate arrangements can be made for resolving such issues as expeditiously as possible.

Respectfully submitted

  
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Kullu Ghara  
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### APPENDIX MARK-UP OF AMENDED SPECIFICATION

[0001] This application claims benefit of United States provisional patent application serial number 60/240,631, filed October 16, 2000, which is herein incorporated by reference. This application contains subject matter that is related to the subject matter described in US patent application serial numbers 09/905,313, 09/905,609, and 09/905,607 [\_\_\_\_\_, \_\_\_\_\_, and \_\_\_\_\_], (Attorney dockets 4744 FET/MDR, 4747 FET/MDR, and 4748 FET/MDR)], filed simultaneously herewith on July 13, 2001, which are each incorporated herein by reference in their entireties.

[0018] The client computer 110 operates to collect defect, defect source, and defect mitigation data from a semiconductor wafer processing system 116<sub>n</sub>. The system 116<sub>n</sub> is coupled to the subscriber equipment 106. The semiconductor wafer processing system 100 contains one or more metrology chambers or stations within which defect and defect source information is generated. The local database 114<sub>n</sub> stores this defect and defect source data. The information from the client database 114, either all or a subset thereof, is communicated to the DKL 102 via the network 104. The subscriber controls the specific amount of data that is communicated to the DKL 102. A distributed defect source analysis system such as the one depicted in Figure 1 is disclosed in US patent application serial number 09/905,607 [\_\_\_\_\_] , filed simultaneously herewith on July 13, 2001, [(Attorney Docket 4748)] and incorporated herein by reference in its entirety.